

## CLEAN VERSION OF THE CHANGES MADE

### In the Claims

1. (Currently Amended) A method for providing a raised feature on a surface of a prototype model characterized by the steps of:

(a) providing a model formed by a stereolithography process, the model having at least one surface on which to provide a raised feature;

(b) coating the surface with a photo resist to a predetermined thickness;

(c) providing means for preventing exposure of a first portion of the photo resist to a radiation source while allowing exposure of a second portion of the photo resist wherein the second portion of the photo resist provides the raised feature;

(d) exposing the surface to a radiation source to chemically alter the second portions of the photo resist; and,

(e) removing the first portion of the photo resist from the surface while leaving the raised feature formed by the exposed photo resist on the surface;

wherein said step of coating said surface with said photo resist includes the steps of applying said photo resist in more than one layer and allowing sufficient drying time between successive layers.

2. (canceled)

3. (canceled)

4. (original) The method of claim 1 further characterized by the step of:

cleaning the surface of the prototype model before the step of coating the surface with the photo resist.

5. (original) The method of claim 1 further characterized by the steps of:  
inspecting the raised feature after the step of removing the first portion of the photo resist; and,

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